

Notice of References Cited	Application/Control No. 10/672,269	Applicant(s)/Patent Under Reexamination WALTON ET AL.	
	Examiner Richard Bueker	Art Unit 1763	Page 1 of 1

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NON-PATENT DOCUMENTS

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*	U	Walton et al., "Ion flux and energy distributions at electrode surfaces in LAPPS" Pulsed Power Plasma Science, 2001. IEEE Conference Record -Abstracts, page 385 (June 2001).
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.